



AF/IDW

Docket No.: M4065.0453/P453-B  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

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In re Patent Application of:  
Eugene P. Marsh et al.

Application No.: 10/657,069

Art Unit: 2822

Filed: September 9, 2003

Examiner: M. Lewis

For: PROCESS FOR LOW TEMPERATURE  
ATOMIC LAYER DEPOSITION OF RH

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**AMENDMENT AFTER FINAL ACTION (37 C.F.R. § 1.116)**

MS AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

**INTRODUCTORY COMMENTS**

In response to the Office Action dated October 5, 2004 (Paper No. 09212004), finally rejecting claims 55 and 56, please amend the above-identified U.S. patent application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 3 of this paper.